

## PRODUCT TECHNICAL BRIEF

# 2L-400C Sputter-Ion Pump, 450 L/s

2L-400C Sputter-Ion Pump, 450 L/s - LeakLab solutions for leak testing, vacuum systems and test equipment.

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## Technical Data

| PARAMETER                                   | PUBLISHED VALUE / INFORMATION                  |
|---------------------------------------------|------------------------------------------------|
| Nitrogen pumping speed                      | 450 L/s                                        |
| Argon pumping speed stated in source record | Approximately 45 L/s                           |
| Ultimate pressure                           | $\leq 1 \times 10^{-8}$ Pa                     |
| Maximum start pressure                      | $\leq 5 \times 10^{-4}$ Pa                     |
| Inlet flange                                | CF150                                          |
| Maximum bakeout temperature                 | <200 °C with magnets / <300 °C without magnets |
| Bakeout jacket                              | Included in the source configuration           |
| High-voltage power supply                   | Included in the source configuration           |
| Indicative dimensions                       | Approximately 500 × 265 × 600 mm               |
| Indicative weight                           | Approximately 153 kg                           |

## Technical and Project Information

Oil-free 2L-400C diode sputter-ion pump for clean high and ultra-high vacuum systems. Stated nitrogen pumping speed: 450 L/s; ultimate pressure:  $\leq 1 \times 10^{-8}$  Pa. The source configuration includes a bakeout jacket and high-voltage power supply. Confirm the complete specification and scope of supply before ordering.

### 2L-400C Diode Sputter-Ion Pump

The 2L-400C is intended for clean high and ultra-high vacuum systems that require oil-free operation and no pump-generated mechanical vibration. A Penning discharge ionizes residual gas; titanium sputtered from the cathodes provides an active surface for pumping reactive gases.

Typical applications include large vacuum chambers, ion sources, coating systems and test stands. Pump-down and commissioning normally require a suitable backing and high-vacuum stage before the ion pump is started.

Actual system pressure depends on gas load, conductance, cleanliness, bakeout, instrumentation and the backing arrangement. For heavy and inert gases, use the operating and regeneration procedures stated by the manufacturer. Confirm the current datasheet, polarity, cable, controller, magnets, bakeout hardware and flange before ordering.

LeakLab can provide integration, leak testing, high-voltage setup and commissioning documentation subject to an agreed project scope.

- Vacuum Pumps Atmosphere-to-High-Vacuum Dry Pumps High-Vacuum Pumping Stations Ion Pumps Diode Ion Pumps for Heavy Gases Triode Ion Pumps for Noble Gases KYKY RV Rotary-Vane Pumps Roots Booster Pumps Screw Vacuum Pumps Tank Evacuation Systems Turbomolecular Pumps
- Atmosphere-to-High-Vacuum Dry Pumps
- High-Vacuum Pumping Stations
- Ion Pumps Diode Ion Pumps for Heavy Gases Triode Ion Pumps for Noble Gases
- Diode Ion Pumps for Heavy Gases
- Triode Ion Pumps for Noble Gases
- KYKY RV Rotary-Vane Pumps
- Roots Booster Pumps
- Screw Vacuum Pumps
- Tank Evacuation Systems
- Turbomolecular Pumps
- Helium Reference Leaks
- Scanning Electron Microscopes
- Leak-Detector Accessories

## WORLDWIDE PROJECT CONTACT

Send the test object or system, operating conditions, target sensitivity or pressure range, applicable standard, destination country, quantity and schedule. LeakLab will review the project scope.

[mail@leaklab.org](mailto:mail@leaklab.org)

Regarding: 2L-400C Sputter-Ion Pump, 450 L/s

Specifications, standards, verification scope, availability and commercial terms must be confirmed for the exact configuration and destination jurisdiction before order or project acceptance.